

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: HAMADA, Yoshitaka et al Conf.:  
Appl. No.: NEW Group:  
Filed: March 25, 2004 Examiner:  
For: POROUS FILM, COMPOSITION AND  
MANUFACTURING METHOD, INTERLAYER  
DIELECTRIC FILM, AND SEMICONDUCTOR DEVICE

PRELIMINARY AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

March 25, 2004

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes:

Amendments to the Specification

Remarks